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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/109,261	06/30/1998	GANG BAI	042390.P5769	3347

7590 01/26/2005  
BLAKELY SOKOLOFF TAYLOR & ZAFMAN  
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EXAMINER

WARREN, MATTHEW E

ART UNIT	PAPER NUMBER
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2815

DATE MAILED: 01/26/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

*AK*

<b>Office Action Summary</b>	Application No.	Applicant(s)	
	09/109,261	BAI, GANG	
	Examiner	Art Unit	
	Matthew E. Warren	2815	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

- 1) ☒ Responsive to communication(s) filed on 01 November 2004.
- 2a) ☒ This action is **FINAL**.                      2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

- 4) ☒ Claim(s) 8-10, 13-17, 20 and 21 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 8-10, 13-17, 20 and 21 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All    b) ☐ Some \* c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- \* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

- |   |   |
|---|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892)                        | 4) <input type="checkbox"/> Interview Summary (PTO-413)                     |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)    | Paper No(s)/Mail Date. _____  |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| Paper No(s)/Mail Date _____   | 6) <input type="checkbox"/> Other: _____                                    |

### DETAILED ACTION

This Office Action is in response to the Amendment filed on November 1, 2004.

#### ***Claim Rejections - 35 USC § 103***

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 8-10, 13-17, 20 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Nagata et al. (US 4,015,281) in view of Momose et al. (US 5,990,516) and Moon (US 5,621,681).

Nagata discloses (col. 3, line 45 – col. 4, line 67) a transistor device having a gate electrode overlying a gate dielectric formed directly on a semiconductor substrate. The dielectric (col. 4, lines 34-49) comprises a first dielectric having a first dielectric constant and a second dielectric having a second dielectric constant different from the first dielectric constant. The first and second dielectrics are scalable for a set of feature size technologies, wherein the first and second dielectric thickness are determined by the formula as recited in claims 8 and 15 (see the expanded formula in col. 4, lines 39-44). The second dielectric ( $\text{Al}_2\text{O}_3$ ) has a greater dielectric constant than the first dielectric ( $\text{SiO}_2$ ) (col. 4, lines 45-49). A third dielectric ( $\text{SiO}_2\text{-P}_2\text{O}_5$ ), having a third dielectric constant may also be used in the composite dielectric layer (col. 4, lines 50-56). Nagata et al. shows all of the elements of the claims except the set of feature size

technologies defined by a gate length in the range of 25-150 nm. Momose et al. discloses (col. 16, 28-48 and col. 16, line 66-col. 17, line 32) a semiconductor device having double layer gate dielectric in which the feature size technology has a gate length of 150 nm (or 0.15  $\mu\text{m}$ ) to form a high performance semiconductor having low power consumption. Momose et al. further discloses (col. 15, lines 13-31) that the gate length can be decreased even more to improve the current drive capability. The gate in one embodiment had a length of 40 nm (0.04  $\mu\text{m}$ ). Momose et al. also discloses (col. 2, lines 52-58) a semiconductor device in which the gate dielectric is less than 1/3 the gate length. The thin gate dielectric improves hot carrier reliability and ultimately the operating characteristics. Nagata and Momose shows all of the elements of the claims except the first dielectric selected from the group of  $\text{HfO}_2$ ,  $\text{BaO}$ ,  $\text{La}_2\text{O}_3$ ,  $\text{Y}_2\text{O}_3$  and  $\text{ZrO}_2$ . Moon shows a (fig. 2) a semiconductor device comprising a first dielectric material (11a) of  $\text{Y}_2\text{O}_3$  and a second dielectric material (12a) of PZT which has a second dielectric constant greater than the dielectric constant of the first dielectric. With this configuration, the yttrium oxide is used as a buffer dielectric and a good quality ferroelectric is formed on the substrate. Moon also shows that the transistor device is isolated from other devices by shallow trench isolation (2). Therefore it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the multi-layer gate dielectric of Nagata for a feature size technology with a desired gate length as taught by Momose to form a high performance transistor having low power consumption. It would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the multiplayer gate dielectric of Nagata and Momose by using  $\text{Y}_2\text{O}_3$  and PZT

as the first and second dielectric layer as taught by Moon to form a good quality ferroelectric on a substrate.

### ***Response to Arguments***

Applicant's arguments filed with respect to claims 8-10, 13-17, 20 and 21 have been fully considered but they are not persuasive because, although Nagata provides a similar formula, Nagata includes silicon dioxide on both sides of the equation and does not provide any limits. However, this argument does not undermine the teachings of Nagata. First, if Nagata's formula were rewritten to solve for  $T_{\text{eff}}/E_{\text{SiO}_2}$  (equivalent to applicant's  $t_{\text{ox}}/k_{\text{ox}}$ ), Nagata's formula would look exactly like applicant's formula with  $T_{\text{SiO}_2}/E_{\text{SiO}_2}$  substituted for applicant's  $t_2/k_2$ . Applicant's claim does not exclude  $\text{SiO}_2$  as the second dielectric and thus Nagata does teach the claimed relationship.

Furthermore, that Nagata does not include a limit as to  $T_{\text{eff}}$  does not undermine the rejection.  $T_{\text{eff}}$  is merely a variable label used to identify the equivalent oxide thickness. It has the same function as " $t_{\text{ox}}$ " used by applicant which carries the same meaning; the equivalent oxide thickness. The difference pointed out by applicant is nothing more than a functional difference; applicant solves for  $t_1/k_1$  and  $t_2/k_2$  based on a given  $t_{\text{ox}}$ , whereas Nagata does not initially give  $t_{\text{ox}}$  ( $T_{\text{eff}}$ ). However, this is merely a difference in starting parameters and does not undermine the structure and formulaic relationship taught by Nagata, the same structure and formula as is instantly claimed. Note also that the instant claim does not specify a certain gate length and thus a certain  $t_{\text{ox}}$  but that  $t_{\text{ox}}$  is based on an unknown "chosen gate length."

The formula is also used to calculate the effective thickness of other materials and therefore the first and second dielectric materials are scalable for a set of feature size technologies as stated in the claims. In all, the cited references teach and make obvious all the elements of the claims, the arguments to the contrary are not persuasive and the rejection is made final.

### ***Conclusion***

**THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire **THREE MONTHS** from the mailing date of this action. In the event a first reply is filed within **TWO MONTHS** of the mailing date of this final action and the advisory action is not mailed until after the end of the **THREE-MONTH** shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than **SIX MONTHS** from the mailing date of this final action.


Any inquiry concerning this communication or earlier communications from the examiner should be directed to Matthew E. Warren whose telephone number is (571) 272-1737. The examiner can normally be reached on Mon-Thur and alternating Fri 9:00-5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

MEW

January 21, 2005

  
GEORGE ECKERT  
PRIMARY EXAMINER